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Supporting Information

Exploration of stable stoichiometries, physical properties and hardness in the Rh-Si system: A first-principles study

Jing-Jing Wang,^a Andreas Hermann,^b Xiao-Yu Kuang,^{a,*} Yuan-Yuan Jin,^a Cheng Lu,^{c,*} Chuan-Zhao Zhang,^a Meng Ju,^a Meng-Ting Si^c and Toshiaki Iitaka^{d,*}

^aInstitute of Atomic and Molecular Physics, Sichuan University, Chengdu, 610065, China

^bCentre for Science at Extreme Conditions and SUPA, School of Physics and Astronomy, The University of Edinburgh, Edinburgh EH9 3JZ, United Kingdom

Department of Physics, Nanyang Normal University, Nanyang, 473061, China

^dComputational Astrophysics Laboratory, RIKEN (The Institute of Physical and Chemical Research) 2-1 Hirosawa, Wako, Saitama 351-0198, Japan



Fig. S1. Relative enthalpies of formation for rhodium silicides. The solid line denotes the ground state convex hull at LDA+U level.

^{*} Correspondence author: scu_kuang@163.com, lucheng@calypso.cn, tiitaka@riken.jp.



Fig. S2. Optimized structures of rhodium silicides: (a) Rh_3Si (*Pnma*), (b) Rh_5Si_2 (*P*4₁2₁2), (c) Rh_3Si_2 (*Cmc*2₁), (d) Rh_3Si_4 (*Pnma*), (e) Rh_2Si_3 (*P*6₃/*mmc*), (f) Rh_3Si_5 (*P*2₁/*c*), (g) $RhSi_2$ (*Cmce*), (h) $RhSi_3$ (*P*6₃*mc*). The green and red spheres represent rhodium and silicon atoms, respectively.



Fig. S3. Calculated total and partial DOSs of (a) Rh_2Si (*Pnma*), (b) Rh_5Si_3 (*Pbam*), (c) RhSi (*Pnma*), and (d) Rh_4Si_5 (*P2*₁/*m*) using LDA+U functional, and (a') Rh_2Si (*Pnma*), (b') Rh_5Si_3 (*Pbam*), (c') RhSi (*Pnma*), and (d') Rh_4Si_5 (*P2*₁/*m*) using GGA-PBE functional, respectively. The Ferm level is at 0 eV.



Fig. S4. Calculated band structures of (a) Rh_2Si (*Pnma*), (b) Rh_5Si_3 (*Pbam*), (c) RhSi (*Pnma*), and (d) Rh_4Si_5 ($P2_1/m$) using LDA+U functional, and (a') Rh_2Si (*Pnma*), (b') Rh_5Si_3 (*Pbam*), (c') RhSi (*Pnma*), and (d') Rh_4Si_5 ($P2_1/m$) using GGA-PBE functional, respectively. The Ferm level is at 0 eV.



Fig. S5. Electron localization function (ELF) maps projected on to (010) plane of $P2_1/m$ phase Rh_4Si_5 . The ELF isosurfaces value is 0.8.

Phase	Space	лн		а			b			С		V	ρ
Flidse	group			Expt.	Theor.		Expt.	Theor.		Expt.	Theor.		
	C2/m	⊵–0.55	8.06			7.47			5.49			14.06	9.94
	Pnma	⊵–0.56	5.36			7.99			5.27			14.12	9.90
Rh₃Si	I4/mcm	⊵–0.55	5.50			5.50			5.50			14.10	9.92
	Pm-3m	⊵–0.38	3.84			3.84			3.87			14.11	9.91
	Fm-3m	⊵–0.25	6.12			6.12			6.12			14.30	9.77
Rh_5Si_2	<i>P</i> 4 ₁ 2 ₁ 2	⊵–0.51	9.53			9.53			8.80			14.25	9.50
	Pnma	⊵–0.82	5.58	5.41 ^{<i>a</i>}		3.99	3.93 ^{<i>a</i>}		7.40	7.38 ^a		13.72	9.44
	I4/mmm	⊵–0.78	4.01			4.01			5.62			15.02	8.62
Ph Si	P-3m1	⊵–0.65	4.19			4.19			4.19			13.81	9.37
11231	<i>P</i> 6 ₃ 22	⊵–0.65	4.18			4.19			5.46			13.82	9.37
	P-62m	⊵–0.11	7.66			7.66			2.81			15.87	8.16
	P6 ₃ /mmc	⊵–0.65	4.19			4.19			5.46			13.82	9.37
	Pbam	⊵–0.86	5.45	5.32 ^{<i>a</i>}		10.32	10.13 ^{<i>a</i>}		3.90	3.90 ^{<i>a</i>}		13.72	9.06
Rh_5Si_3	P6 ₃ /mcm	⊵–0.44	7.39			7.39			4.99			14.78	8.41
	la-3d	⊵–0.44	8.40			8.40			8.40			14.24	8.73
Rh_3Si_2	<i>Cmc</i> 2 ₁	⊵–0.68	13.29			11.43			7.50			14.25	8.50
	P21/c	⊵–0.88	4.63	4.59 ^b		4.62	4.57 ^b		5.64	5.53 ^b		13.66	7.96
DHC	Pnma	⊵–0.91	5.60	5.56 ^b	5.60 ^c	3.11	3.70 ^b	3.11 ^c	6.45	6.38 ^b	6.45 ^c	14.05	7.74
1131	P2 ₁ 3	⊵–0.88	4.70	4.68 ^b	4.73 ^c	4.73	4.68 ^b	4.73 ^c	4.73	4.68 ^b	4.73 ^c	13.26	7.40
	Pm-3m	⊵–0.63	2.90	2.96 ^d		2.90	2.96 ^d		2.99	2.96 ^d		13.34	8.15
Rh_4Si_5	P2 ₁ /m	⊵–0.82	12.47			3.55			6.01			14.53	7.01
Rh_3Si_4	Pnma	⊵–0.56	20.57			4.45			4.50			14.71	6.79
	Pbcn	⊵–0.61	10.58			9.09			6.03			14.50	6.65
Rh_2Si_3	P-4c2	⊵–0.56	5.69			5.69			8.99			14.58	6.61
	P6 ₃ /mmc	⊵–0.62	3.76			3.76			12.52			15.36	6.27
Rh_3Si_5	P21/c	⊵–0.65	6.48			14.24			11.64			14.99	6.22
	Cmce	⊵–0.55	6.98			6.98			8.09			15.46	5.70
RhSi ₂	P4/mmm	⊵–0.42	2.93			2.93			5.25			15.08	5.84
	Fm-3m	⊵–0.55	5.71			5.71			5.71			15.49	5.68
PhSi	P6₃mc	⊵–0.03	4.81			4.81			6.36			15.95	4.87
NI 313	P6 ₃ /mmc	⊵–0.02	4.36			4.36			7.44			15.30	5.08
^a Ref. 1, ¹	^{<i>a</i>} Ref. 1, ^{<i>b</i>} Ref. 2, ^{<i>c</i>} Ref. 3, ^{<i>d</i>} Ref. 4.												

Table S1. Calculated lattice parameters, a, b, and c (Å); volume (V in Å³) per atom; density (g/cm³), and relative total energy per chemical formula unit (ΔH in eV) of rhodium silicides with various stoichiometries, compared with experimental and other theoretical data.

	Structure	Lattice parameters	Atom	Positions(<i>x, y, z</i>)			
				x	у	Z	
			Rh1(8d)	0.1818	0.0227	0.3143	
Rh₃Si	Pnma	<i>a</i> =10.72, <i>b</i> = 7.99, c=5.27	Rh2(4c)	0.0007	0.2500	0.9538	
			Si1(4c)	0.9441	0.2500	0.4882	
			Rh1(8b)	0.4421	0.1687	0.3593	
			Rh2(8b)	0.1722	0.2211	0.1710	
		a=9.53 $b=9.53$ $c=8.80$	Rh3(8b)	0.3886	0.4244	0.1814	
Rh _e Sia	P4.2.2		Rh4(8b)	0.3816	0.0292	0.0615	
1115012	, ,1=1=	u 9.99, 6 9.99, 6 9.90	Rh5(4a)	0.1622	0.1622	0.5000	
			Rh6(4a)	0.4291	0.4291	0.5000	
			Si1(8b)	0.5016	0.2504	0.0433	
			Si2(8b)	0.3885	0.2057	0.6187	
		a=5.58, b=3.99, c=7.40	Rh1(4c)	0.8433	0.2500	0.0713	
Rh₂Si	Pnma		Rh2(4c)	0.9755	0.2500	0.6927	
			Si1(4c)	0.2735	0.2500	0.1056	
			Rh1(2c)	0.0000	0.5000	0.0000	
			Rh2(4g)	0.1606	0.2120	0.0000	
Rh_5Si_3	Pbam	<i>a</i> =5.45, <i>b</i> =10.32, <i>c</i> =3.90	Rh3(4h)	0.3330	0.3931	0.5000	
			Si1(4h)	0.4082	0.1558	0.5000	
			Si2(2a)	0.0000	0.0000	0.0000	
		a=8.16, b=8.16, c=6.92	Rh1(4)	0.2902	0.0562	0.5180	
			Rh2(4)	0.2912	0.0534	0.9000	
			Rh3(4)	0.4439	0.0495	0.2170	
	Cmc2 ₁		Rh4(4)	0.6799	0.3151	0.2250	
			Rh5(2)	0.0000	0.0000	0.0000	
			Rh6(2)	0.2345	0.2345	0.0240	
Rh_3Si_2			Rh7(2)	0.2330	0.2330	0.4000	
			Rh8(2)	0.3814	0.3814	0.7140	
			Si1(4)	0.1790	0.0610	0.2140	
			Si2(4)	0.4860	0.1820	0.5060	
			Si3(4)	0.4940	0.1920	0.9200	
			Si4(2)	0.1570	0.1570	0.7120	
			Si5(2)	0.4090	0.4090	0.2180	
RhSi	Pnma	a=5.60, b=3.11, c=6.45	Rh1(4c)	0.0029	0.2500	0.2032	
		a 0.00, 0 0.11, 0 0.10	Si1(4c)	0.1849	0.2500	0.5561	
			Rh1(2e)	0.0499	0.2500	0.2091	
			Rh2(2e)	0.2731	0.2500	0.1070	
			Rh3(2e)	0.5001	0.2500	0.2994	
		a=12.47, b=3.55, c=6.01	Rh4(2e)	0.7308	0.2500	0.2866	
Rh_4Si_5	<i>P</i> 2 ₁ /m		Si1(2e)	0.6350	0.2500	0.6385	
			Si2(2e)	0.4221	0.2500	0.8933	
			Si3(2e)	0.2237	0.2500	0.4649	
			Si4(2e)	0.9229	0.2500	0.4876	
			Si5(2e)	0.1395	0.7500	0.9790	
			Rh1(4c)	0.0486	0.2500	0.5239	
		a=20.56, b=4.45, c=4.50	Rh2(4c)	0.2136	0.2500	0.0464	
Rh₂Si₄	Pnma		Rh3(4c)	0.3651	0.2500	0.2606	
			Si1(4c)	0.1690	0.2500	0.5500	
			Si2(4c)	0.4384	0.2500	0.2096	
			Si3(4c)	0.4384	0.2500	0.2096	

Table S2. Optimized Structural Parameters for the rhodium silicides.

			Si4(4c)	0.4089	0.7500	0.5137
		a=3.76, b=3.76, c=12.52	Rh1(4f)	0.3333	0.6666	0.1391
Rh_2Si_3	P6 ₃ /mmc		Si1(4f)	0.3333	0.6666	0.9423
			Si2(2b)	0.0000	0.0000	0.2500
			Rh1(4e)	6.4780	14.2392	11.635
			Rh2(4e)	0.5642	0.5944	0.3961
			Rh3(4e)	0.9517	0.7525	0.2446
			Rh4(4e)	0.0833	0.9553	0.2722
			Rh5(4e)	0.2297	0.6667	0.1321
			Rh6(4e)	0.2334	0.8345	0.9940
			Si1(4e)	0.9279	0.8433	0.0692
Dh Ci	D7 /c	a = 6.47 $b = 14.24$ $c = 11.64$	Si2(4e)	0.7456	0.4890	0.5759
1113015	1290	u -0.47, b-14.24, c-11.04	Si3(4e)	0.8648	0.6104	0.3292
			Si4(4e)	0.3289	0.9433	0.1648
			Si5(4e)	0.8565	0.6123	0.1087
			Si6(4e)	0.3519	0.9355	0.5086
			Si7(4e)	0.9495	0.6481	0.9068
			Si8(4e)	0.2547	0.9879	0.7050
			Si9(4e)	0.3770	0.7504	0.8548
			Si10(4e)	0.5524	0.7777	0.1965
			Rh1(8d)	0.2501	0.0000	0.5000
RhSi.	Cmce	a = 11.11 $b = 8.05$ $c = 8.09$	Rh2(8f)	0.5000	-0.2464	0.2534
NI JIZ	Child	u -11.41, 0-0.00, 0-0.00	Si1(16g)	0.1248	-0.2498	0.4977
			Si2(16g)	0.3745	0.0025	0.2499
RhSi a	P6,mc	a =4.81, b=4.81, c=6.36	Rh1(2b)	0.3333	0.6666	0.2522
KNSI3	103110		Si1(6c)	0.8333	0.1666	0.0822

Phase	Space	method	∆ <i>H</i> (eV)	a (Å)	b (Å)	<i>c</i> (Å)	V (ų)	ρ (g/cm ³)
Rh₂Si	Pnma	GGA	-0.82	5.58	3.99	7.40	13.72	9.44
		LDA+U	-0.82	5.63	3.97	7.32	13.62	9.50
		Expt.		5.41 ^a	7.38 ^a	7.38 ^a		
Rh_5Si_3	Pbam	GGA	-0.86	5.45	10.32	3.90	13.72	9.06
		LDA+U	-0.88	5.47	10.26	3.88	13.61	9.13
		Expt.		5.32 ^a	10.13 ^{<i>a</i>}	3.90 ^a		
RhSi	Pnma	GGA	-0.91	5.60	3.11	6.45	14.05	7.74
		LDA+U	-0.91	5.62	3.12	6.49	14.22	7.65
		Expt.		5.56 ^b	3.70 ^b	6.38 ^b		
Rh_4Si_5	P2 ₁ /m	GGA	-0.82	12.47	3.55	6.01	14.53	7.01
		LDA+U	-0.86	12.45	3.55	5.98	14.44	7.05
^{<i>a</i>} Ref. 1,	^b Ref. 2,							

Table S3. Calculated (at GGA and LDA levels) and experimental lattice parameters, a, b, and c; volume V per atom, density, and relative total energy per chemical formula unit ΔH of rhodium silicides with various stoichiometries.

Structure	Band	d ^µ (Å)	P^{μ}	f_m	$v_b^{\mu}(Å^3)$	H_{v}^{μ}	H _v
Rh ₂ Si	Si-Rh	2.415	0.130	0.321	3.812	7.026	11.9
(Pnma)		2.423	0.370	0.113	3.851	25.676	
(2.471	0.415	0.100	4.086	26.458	
		2.480	0.300	0.139	4.127	18.002	
		2.520	0.340	0.123	4.331	19.186	
		2.851	0.110	0.379	6.271	2.370	
Rh_5Si_3	Si-Rh	2.357	0.150	0.099	3.241	14.090	12.0
(Pbam)		2.369	0.130	0.114	3.292	11.697	
, <i>,</i>		2.420	0.425	0.035	3.508	37.476	
		2.443	0.370	0.040	3.608	30.962	
		2.483	0.340	0.044	3.792	26.096	
		2.577	0.360	0.041	4.239	23.003	
		2.725	0.040	0.371	5.009	1.269	
		2.750	0.105	0.141	5.150	4.344	
RhSi	Si-Rh	2.437	0.310	0.003	4.270	20.346	14.7, 14.8 ^a
(Pnma)		2.444	0.350	0.003	4.306	22.655	
v - <i>j</i>		2.526	0.225	0.005	4.756	12.323	
	Si-Si	2.691	0.260	0.004	5.749	10.387	
Rh₄Si₅	Si-Rh	2.324	0.435	0.002	3.943	32.657	20.1
(<i>P</i> 2₁/m)		2.338	0.010	0.071	3.943	0.698	
(1) /		2.400	0.410	0.002	3.943	30.777	
		2.411	0.420	0.002	3.943	31.529	
		2.428	0.220	0.003	3.943	16.490	
		2.437	0.330	0.002	3.943	24.761	
		2.438	0.350	0.002	3.943	26.265	
		2.462	0.435	0.002	3.943	32.657	
		2.463	0.095	0.007	3.943	7.090	
		2.485	0.365	0.002	3.943	27.393	
		2.486	0.260	0.003	3.943	19.498	
		2.499	0.040	0.018	3.943	2.954	
		2.520	0.395	0.002	3.943	29.649	
		2.526	0.275	0.003	3.943	20.625	
		2.612	0.385	0.002	3.943	28.897	
		2.687	0.370	0.002	3.943	27.769	
	Si-Si	2.774	0.235	0.003	3.943	17.618	
		2.779	0.250	0.003	3.943	18.746	
		2.596	0.360	0.002	3.943	27.017	
		2.601	0.400	0.002	3.943	30.025	
		2.651	0.295	0.002	3.943	22.129	
Si (Fd-3m)	Si-Si	2.374	0.730	0.001	10.297	11.074	11.1
^a Ref.3							

Table S4. Calculated bond length d^{μ} , Mulliken overlap population P^{μ} , f_m , bond volume, and Vickers hardness H_{ν} (GPa) for rhodium silicides with different structures.

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